

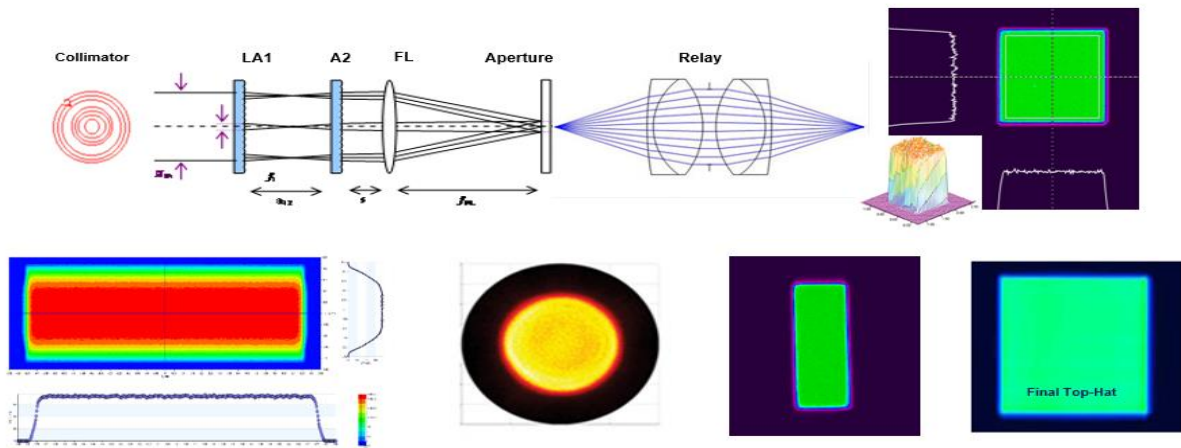
The Local Laser Annealing System

Specification sheet

□ **Mechanical and optical specification**

| | |
|---------------------------------------|--------------------------|
| Machine Size (WxHxD) (Including EFEM) | 2,280 x 2,180 x 3,210 mm |
| Wavelength | 1,064nm/532nm/etc. |
| Output power | Depending on application |
| Repetition rate | Depending on application |
| Beam size | Min. 50x50 um (Top-hat) |
| Uniformity | <5% |
| Beam edge steepness | <20um |

□ **Optical system**



□ **Stage (X,Y,T) specification**

| Isolation table | X, Y | Z | T |
|-----------------|-----------|--------|-----------|
| Stroke | 400x350um | 5mm | 185mm |
| Accuracy | ±1um | ±1um | ±30arcsec |
| Speed | 500mm/s | 50mm/s | 0.5rms |
| Jitter | ±4um | ±20um | - |



Stage for annealing system

